

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L3	219	silicon-rich adj oxide	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/06 17:59
L4	987	438/240.ccls.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/06 17:30
L5	210	438/263.ccls.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/06 17:33
L6	2791	438/624.ccls.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/06 17:33
L7	79	silicon-rich adj oxide	US-PGPUB	OR	ON	2005/08/06 17:59
S1	5	interlayer adj dielectric and silicon-rich adj silicon and refractive adj index	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/29 18:08
S2	6	("5863462" "5935705" "6090358" "6198216" "6444568" "6475895" "2001/0046731" "2003/0096475").PN.	USPAT	OR	OFF	2004/09/14 15:30
S3	484	sonos	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2004/09/14 15:52
S4	25	sonos and interlayer adj dielectric	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/14 15:57
S5	237	transistor and interlayer adj dielectric and silicon adj oxide adj layer	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/14 16:24
S6	243	gate and interlayer adj dielectric and silicon adj oxide adj layer	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/14 16:25
S7	997	gate and interlayer adj dielectric and planariz\$5	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/14 16:25

S8	728	gate and interlayer adj dielectric and planariz\$5 and remov\$5 same layer	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/14 16:26
S9	4	gate and silicon-rich adj silicon adj oxide and interlayer	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/14 16:47
S10	23	gate and silicon-rich adj silicon adj oxide	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/14 16:50
S11	21	interlayer adj dielectric and tunnel adj oxide and BPSG and ONO	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/15 20:12
S12	1	silicon-rich silicon oxide and Uv radiation	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2004/12/22 17:24
S13	0	silicon-rich silicon oxide and Uv radiation and opaque	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2004/12/22 18:25
S14	0	silicon doped silicon oxide and Uv radiation and opaque	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2004/12/22 18:47
S15	0	silicon doped silicon oxide and opaque	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	OFF	2004/12/22 18:47
S16	6	Uv blocking layer and silicon oxide	USPAT; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2005/02/17 17:27
S17	4	("5290727" "5602056" "20030096 476").PN.	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/29 18:10
S18	217	silicon-rich adj oxide	USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/06 17:12